

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants: DIETER W. POHL ET AL. Docket No.: 01-406
Serial No.: 09/904286 Examiner : Olsen
Filed : 7-12-01 Art Unit : 1744
For : METHOD AND APPARATUS FOR THE CONTROLLED
CONDITIONING OF SCANNING PROBES

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INFORMATION DISCLOSURE STATEMENT

Hon. Commissioner of Patents and Trademarks
United States Patent & Trademark Office
Washington, D.C. 20231

Dear Sir:

In accordance with the requirements of 37 C.F.R. 1.97 and 1.98, Applicants hereby submit the prior art documents listed hereinbelow, copies enclosed, which prior art was cited in the corresponding European Search Report.

- (1) U.S. Patent No. 5,038,034 for SCANNING TUNNELING MICROSCOPE, By Shigeto Fujita, Patented August 6, 1991.

This reference discloses a scanning tunneling microscope which is arranged to cause a tunneling current to flow through a gap between a specimen and a probe housed in a

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vacuum chamber, and is provided with a working arrangement for reshaping the probe.

- (2) U.S. Patent No. 5,548,117 for PROBE FOR A SCANNING TUNNELING MICROSCOPE AND METHOD OF MANUFACTURING A PROBE, By Tohru Nakagawa, Patented August 20, 1996. This reference discloses a probe for use in a scanning tunneling microscope which can measure a macromolecule, i.e., a protein molecule.
- (3) U.S. Patent No. 5,838,005 for USE OF FOCUSED ION AND ELECTRON BEAMS FOR FABRICATING A SENSOR ON A PROBE TIP USED FOR SCANNING MULTIPROBE MICROSCOPY AND THE LIKE, By Arunava Majumdar et al., Patented November 17, 1998. This reference discloses nanometer holes which can be reliably and repeatedly defined in the tips of cantilevered probes and used in various types of scanning multiprobe microscopy by defining the hole within a layer disposed on the tip using focused electron or ion beams.
- (4) U.S. Patent No. 5,686,207 for METHOD OF FORMING AND REPAIRING A MASK FOR PHOTOLITHOGRAPHY, By Masayuki Suda et al., Patented November 11, 1997. This reference discloses a method of forming a mask for photolithography which

comprises forming a transparent conductive film on a transparent substrate.

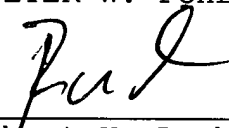
The undersigned submits the above-identified references for independent consideration by the Examiner and does not make any admission that these references are or are not material to the present invention or that these references are or are not prior art with respect to the present invention.

If any charges are required in connection with this submission, it is requested that they be charged to Deposit Account No. 02-0184.

Respectfully submitted,

DIETER W. POHL ET AL.

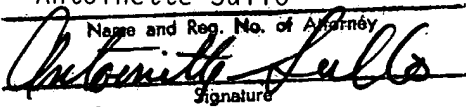
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